



JPW

Docket No. 263788US2PCT

IN RE APPLICATION OF: Keisuke KAWAMURA, et al.

SERIAL NO: 10/519,475

FILED: December 28, 2004

FOR: APPARATUS FOR PLASMA PROCESSING, METHOD OF PROCESSING SUBSTRATE THEREWITH,
APPARATUS FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION, AND METHOD FOR FILM
FORMATION THEREWITH

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

Transmitted herewith is an amendment in the above-identified application.

- ☒ No additional fee is required
- ☐ Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.
- ☐ Additional documents filed herewith:

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	11	MINUS	20	0	x \$50 =	\$0.00
INDEPENDENT	4	MINUS	4	0	x \$210 =	\$0.00
APPLICATION SIZE		MINUS	100	0 (each addtl. 50 sheets)	x \$260 =	\$0.00
		<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS			+ \$370 =	\$0.00
		TOTAL OF ABOVE CALCULATIONS				\$0.00
		<input type="checkbox"/> Reduction by 50% for filing by Small Entity				\$0.00
		TOTAL				\$0.00

- ☐ A check in the amount of \$0.00 is attached.
- ☐ Credit card payment form is attached to cover the fees in the amount of \$0.00
- ☒ Please charge any additional Fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.
- ☒ If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

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DOCKET NO: 263788US2PCT



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :
KEISUKE KAWAMURA, ET AL. : EXAMINER: ARANCIBIA, M.G.
SERIAL NO: 10/519,475 :
FILED: DECEMBER 28, 2004 : GROUP ART UNIT: 1763
FOR: APPARATUS FOR PLASMA :
PROCESSING, METHOD OF
PROCESSING SUBSTRATE
THEREWITH, APPARATUS FOR
PLASMA-ENHANCED CHEMICAL
VAPOR DEPOSITION, AND METHOD
FOR FILM FORMATION THEREWITH

AMENDMENT UNDER 37 C.F.R. § 1.111

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Office Action dated July 27, 2007, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 7 of this paper.